

Appl. No. : **Unknown**
Filed : **Herewith**

IN THE CLAIMS:

Please amend the following claims as indicated:

Please cancel ~~Claims~~ 1-16 as originally filed and Claims 1-12 as amended during international examination without prejudice.

Please add the following new claims:

17. (New) A method of rotating a disc-shaped object, comprising:

floatingly positioning a disc-shaped object in a substantially horizontal position in a compartment including a horizontal top part located above said object and a horizontal bottom part located below said object, wherein at least one of said top part and bottom part includes a pattern of grooves and gas-introduction holes located in said part including said grooves and oriented perpendicular to a surface of said part including said grooves;

injecting a gas flow into the compartment through the gas-introduction holes; and

diverting said gas flow after injection into said compartment into a direction along said grooves to impart rotation to said object, wherein said gas flow provides for a rotation generating component that is tangential to a periphery of said object.

18. (New) The method of Claim 17, wherein rotation generating gas flow is introduced at an upper major surface of said object and a further gas flow is directed along a lower planar surface of the object for supporting said object in a floating manner.

19. (New) The method of Claim 17, wherein said gas flow giving rotation to said object is controlled using a pattern of spiral grooves, wherein an origin of said spiral grooves lies in proximity of a desired center of the object, and an end of said spiral grooves lies in proximity of a periphery of said object.

20. (New) The method of Claim 17, wherein the said gas flow giving rotation to said object is controlled using a pattern of grooves comprising circle segments, wherein each of said

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circle segments is provided with at least one gas-introduction hole arranged in proximity of one end of said circle segments.

21. (New) The method of Claim 20, wherein each of said circle segments provided with at least one gas-introduction hole arranged in proximity of one end of said circle segments is provided with at least one gas-discharge hole arranged in proximity of an opposing end of said circle segments.

22. (New) A reactor for the floating, rotational treatment of semiconductor wafers, comprising a top part and a bottom part between which a chamber for accommodating a wafer is delimited, said top part and said bottom part being provided with gas-introduction holes for discharging gas into said chamber, wherein said gas-introduction holes are oriented essentially perpendicular to a surface of the top part and a surface of the bottom part, and that a pattern of grooves is arranged in the surface of at least one of said parts, said pattern of grooves being designed to impart to gas entering into said chamber from said gas-introduction holes a flow component which is tangential to a periphery of a wafer held within said chamber.

23. (New) The reactor of Claim 22, wherein said pattern of grooves comprises a pattern of spiral shaped grooves, wherein an origin of said spiral lies in proximity of a desired center of the wafer, and wherein an end of said spiral lies in proximity of a desired periphery of the wafer.

24. (New) The reactor of Claim 23 wherein in at least one of the parts having grooves in its surface the gas-introduction holes are arranged along a spiral line, wherein the origin of said spiral lies in proximity of the desired center of the wafer, and wherein the end of said spiral lies in proximity of the desired periphery of the wafer.

25. (New) The reactor of Claim 23, wherein said gas-introduction holes are arranged next to said spiral shaped grooves.

26. (New) The reactor of Claims 23, wherein said spiral shaped grooves are designed so as to widen in a direction of a flow of gas.

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27. (New) The reactor of Claim 22, wherein said pattern of grooves comprises circle segments, and wherein each of said circle segments is provided with at least one gas-introduction hole arranged in proximity of one end of said circle segments.

28. (New) The reactor of Claim 27, wherein each of said circle segments, which is provided with at least one gas-introduction hole arranged in proximity of one end of said circle segments, has at least one gas-discharge hole arranged in proximity of an opposing end of said circle segments.

REMARKS

The foregoing amendments are to more closely conform the application to U.S. practice.

No new matter is added. Entry of the amendments is respectfully requested.

Respectfully submitted,

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Dated: 9/17/01

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